

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	10	chung-henry.in. and (hard near mask\$3)	US-PGPUB; USPAT	OR	OFF	2006/05/13 11:31
L2	67991	(etch\$3 same (silicon or poly adj silicon)) same mask\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/13 11:33
L3	4725	L2 same ((hard near mask\$3) same (oxide or nitride))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/13 11:33
L4	1668	L3 same photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/13 11:33
L5	8	L4 and (trench\$3 near effect)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/13 11:33
L6	11	L4 and (micro near trench\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/05/13 11:46